

Sheet 1 of 1

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INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

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(Usual approval shows if necessary)

Document Number (Optional)

TSMC-03-305

Application Number

10/764,913

Applicant

Bor-Wen Chan et al.

Filing Date

01/26/04

Group Art Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	TITLE	CLASS	SUBCLASS	FILED DATE & APPROXIMATE
ICLI	6500755	12/31/02	Dakshina-Murthy et al.	438	637	12/6/00
	6482726	11/19/02	Aminpur et al.	438	585	10/17/00
	6548423	4/15/03	Plat et al.	438	780	1/16/02
	6492068	12/10/02	Suzuki	430	5	1/7/00
ICLI	6541360	4/16/03	Plat et al.	438	585	4/30/01

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

ICLI	U.S. Patent Application Publication US 2002/0164543 A1
ICLI	Lin et al., Publication Date 11/7/02, "Bi-layer Photolithographic Process", US Class 430/313, filed 7/2/01.

EXAMINER

/Calvin Lee/

DATE CONSIDERED

(11/13/2007)

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